



Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown

## U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	3,743,842	07/03/1973	Smith, H.I., et al.	250	320	01/14/79
	4,310,743	01/12/1982	Seliger, R.L.	219	121 EB	09/24/79
	4,325,779	04/20/1982	Rossetti, J.J.	156	651	11/17/81
	4,383,026	05/10/1983	Hall, T.M.	430	325	08/24/81
	4,450,358	05/22/1984	Reynolds, G.O.	250	492.1	09/22/82
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	4,516,253	05/07/1985	Novak, W.T.	378	034	04/25/83
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	4,576,678	03/18/1986	Shibata, H.	156	643	09/13/84
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	5,861,113	01/19/1999	Choquette, S.J., et al.	264	1.24	08/01/96

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**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No
	1196749	01/30/1988	European	G11B	7/26	
	244884	03/28/1986	European	B29C	33/64	
	401196749	08/08/1989	Japan	G11B	7/26	
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	Broere, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter</u> 33 (5), 1978 American Institute of Physics, 392-394, (September 1, 1978)
	Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science</u> , Vol 272, 85-87, (April 5, 1996)
	Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering</u> 11, Elsevier Science Publishers B.V., 317-321, (1990)
	Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter</u> 62 (23), 1993 American Institute of Physics, 2989-2991, (June 7, 1993)

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\*Substitute Disclosure Statement Form (PTO-1449)

\*\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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**OTHER DOCUMENTS**

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	Hara, et al., "An Alignment Technique Using Diffracted Moire Signals", <u>J. Vac. Sci. Technol. B 7 (6)</u> , 1989 American Vacuum Society, 1977-1979, (Nov./Dec. 1989)
	Harmening, et al., "Molding of Threedimensional Microstructures by the Liga Process", <u>Proceedings IEEE : Micro Electro Mechanical Systems</u> , Travemunde, Germany, 202-207, (1992)
	Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> , 145-149, (1992)
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